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Abstract

The invention describes an apparatus used for chemical vapor deposition of materials on substrates such as semiconductor wafers, comprising:

a circular, substantially planar susceptor having an upper surface for centrally receiving a substrate for chemical deposition purposes; and

a susceptor ring structure separate from said susceptor having an inner diameter slightly larger than the outer diameter of said susceptor to enable the positioning of said ring structure in substantially concentric relation with the susceptor and to enable said susceptor to be rotated while the ring structure is fixed, including a passage for supporting one or more sensors close to the periphery of the susceptor to monitor the temperature adjacent the periphery of the susceptor.

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